REMARKS

In the non-final office action mailed December 11, 2006, claims 1-27 were

examined and stand rejected. Claims 28-40 have been canceled without prejudice to

consideration in a continuing application. The abstract and claim 6 have been amended.

A declaration of the sole inventor in accordance with 37 CFR §1.131 accompanies this

response (the "Declaration"). Reconsideration of the present application as amended in

view of the remarks that follow is respectfully requested.

Amendment to the Specification

The specification was objected to because of a misspelling in line one of the

abstract. Line 1 of the abstract has been amended as suggested in the Office Action.

Also, guidelines were presented regarding the preferred layout of the specification. It is

believed the current format of the application as amended should be acceptable.

Claim Rejection Under §112, paragraph 2

Claim 6 was rejected under 35 USC §112, second paragraph as being indefinite

due to a lack of antecedent basis for "said forming" in line 2. Accordingly, "forming"

has been replaced with "performing" which is introduced in base claim 1. It is believed

that this amendment addresses concerns raised under §112, paragraph 2.

Claim Rejections based on Prior Art

Claims 1-3, 5, 6, 8-11, 13-8, 20-22, and 26-27 were rejected under 35 USC

§102(e) as being anticipated by Ross et al. (App. Phys. Lett. 2003 83(6) pp1225-1227)

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(hereinafter "Ross et al."). Claim 3 was rejected under 35 USC §103(a) as being

unpatentable over Ross et al. Claims 4, 12, 19, 23-25 were rejected under 35 USC

§103(a) as being unpatentable over Ross et al. in view of Choi (WO 00/08225)

(hereinafter "Choi"). Finally, claim 7 was rejected under 35 USC §103(a) as being

unpatentable over Ross et al. in view of U.S. Patent number 5,980,983 to Gordon

(hereinafter "Gordon").

Rule 1.131 Declaration

Grounds of rejection asserted against claims 1-27 of the present application are

based on Ross et al., which is being asserted as anticipatory of some claims and as the

primary reference against others in an obviousness context. The Declaration enclosed

herewith is submitted in compliance with 37 CFR §1.131. The indicated date of

publication of the Ross et al. reference is August 11, 2003 (the "Publication Date"). The

present application was filed little more than five weeks later on September 19, 2003 (the

"Filing Date"). As established by the enclosed Declaration, the inventors conceived of

the inventions defined by claims 1-27 well before the Publication Date.

Furthermore, the Declaration and its exhibits establish substantially continuous

and diligent efforts to prepare and file the subject application from a time before the

Publication Date through the Filing Date. Accordingly, the Declaration establishes the

requisite conception and due diligence from a time prior to the Publication Date to the

subsequent constructive reduction to practice that resulted from filing of the Application.

Moreover, an actual reduction to practice is further established prior to the Publication

Date by the Declaration at least as to the rejected independent claims. Therefore, it is

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respectfully submitted that Ross et al. has been overcome in accordance with 37 CFR §1.131. In addition, further reasons support allowance of the claims over the grounds of rejection based on Ross et al. as set forth in the following comments.

Rejections over Ross et al.

Claims 1-3, 5, 6, 8-11, 13-8, 20-22, and 26-27 were rejected under 35 USC §102(a) as being anticipated by Ross et al. and claim 3 was rejected under 35 USC §103(a) as being unpatentable over Ross et al. Ross et al. discloses a film that "consists of high-aspect-ratio 14-15 nm diameter copper columns embedded in, and separated by, matrix of carbonaceous residue" (column 2, lines 12-14) by a process using "ion-induced chemical vapor deposition" (column 1, line 1) at "25°C using 500eV ions at a flux of 10.6μA/cm² and with a local copper(I)hfacVTMA pressure of about 0.5mTorr" (column 2, lines 10-11).

Anticipation under 35 U.S.C. § 102(a) requires that each and every element as set forth in a claim be disclosed in a single prior art reference. The features of claim 1 include the vapor deposition of an organometallic to form copper nanostructures that are freestanding during formation. Ross et al. fails to disclose, teach, or suggest such features. The Office Action appears to assert that "freestanding" is defined by the applicant as being vertically aligned without the use of a template or patterning device in an exclusive manner. It is surmised that the Office Action relies on page 3, lines 2-3 of the present application, which states: "As used herein 'freestanding' refers to the capability of vertically extending from a base or substrate without support from a template or patterning device." As depicted in Figure 1 of Ross et al., the nanocellular

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copper rods are separated by and surrounded with a supporting carbonaceous material in

contact therewith. Accordingly, this carbonaceous material functions as a device

defining the pattern occupied by the nanocellular rods (a patterning device) or otherwise

provides a template during formation. Indeed, when Ross et al. describes conditions to

remove carbon within XPS detection limits (H-atom assisted deposition), a noncolumnar

equiaxed microstructure resulted – not a nanostructure as defined in claim 1 (See, Ross et

al., column 4, page 2, first sentence). This distinction buttresses the role of the

carbonaceous material as a patterning device and/or template needed to provide the

observed nanocellular rods.

Moreover, while the present application clarifies what "freestanding" refers to, it

does not restrictively define it. The role of the carbonaceous material at the boundaries of

the rods defies any assertion that the Ross et al. rods are freestanding during formation.

Accordingly, claim 1 is not anticipated. Likewise, the other rejected independent claims

are not anticipated for at least the same reasons.

Further reasons also support the novelty of rejected independent claim 9 which

discloses the deposition of monocrystalline nanowires that are freestanding, among other

things. The Office Action states that the monocrystalline structures are inherent in

performing the process described by Ross et al. because it is the same as that claimed. To

the contrary, the method defined by claim 9 encompasses many different processes. In

one nonlimiting example, the method of claim 9 can encompass a process that includes

the organometallic compound recited in its dependent claim 12. By its own terms, the

Office Action recognizes that Ross et al. does not disclose such a compound. In fact,

many such distinctions can be made, including these given in connection with the claim 1

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rejection. Thus, the method of claim 9 and the specific process of Ross et al. cannot be

considered "the same" or identical. Indeed, Ross et al. focuses on the nanocellular

growth of two phases in a single film that results in a combination of rods surrounded by

carbonaceous material (entire document). Furthermore, inherency requires that the

asserted feature must be a necessary consequence of the express disclosure of Ross et al.

There is no evidence to support such a conclusion.

In addition to the reasons supporting novelty of the base claims, further reasons

support various dependent claims rejected on the same grounds. For example, claims 2

and 17 both include a monocrystalline feature that is further patentable for at least the

reasons this feature is patentable as described in connection with independent claim 9. In

another example, dependent claims 10, 22 and 27 recite incorporation into at least one of

an integrated circuit device, a device to process signals having a frequency of 100 GHz or

more, a displayed device, and a sensing device. The Office Action asserts that because

Ross et al. tersely refers to other features for circuit and x-ray mask repair that it

somehow discloses the claims features. To the contrary, a "circuit" as recited in Ross et

al. encompasses any of a number of different types of discrete component circuitry

structures and cannot be reasonably construed to specifically disclose incorporation into

an integrated circuit device as defined by these claims. Notably, there is no reference

given in the Office Action that discloses a device to process signals having a frequency of

100 GHz or more, a display device, or a sensing device. Thus, numerous additional

reasons support novelty of rejected dependent claims.

Response to Office Action Application No. 10/664,431 **Obviousness Rejection of Claim 3**

In addition, claim 3 is not unpatentable over Ross et al. because of the distinctions

discussed above and the fact that a notion to grow individual nanowires with a longer

second dimension is not the same as an actual process which is capable of reducing this

to practice. The Office Action refers to the second dimension and then references the

growth rate information in Ross et al. which does not disclose any information as to the

length of the columnar microstructures. Ross et al. only disclosed an ambiguous "high-

aspect-ratio" characterization (Figure 1b). Indeed, it is highly speculative that the Ross et

al. process could provide such features. Consequently, there would be no reasonable

expectation of success as required to establish obviousness.

Obviousness Rejections of Other Claims

Claims 4, 7, 12, 19, 23-25 were rejected under 35 USC §103(a) as being obvious.

These claims are patentable for at least the same reasons that the corresponding base

claims are novel. Furthermore, the requisite motivation to combine the references in the

manner asserted has not been given as required to establish obviousness.

Conclusions

In view of the forgoing, it is believed that claims 1-27 are in condition for

allowance. Reconsideration of the present application as amended is respectfully

Response to Office Action Application No. 10/664,431 requested. The Examiner is invited to contact the undersigned by telephone to address any outstanding matters concerning the present application.

Respectfully submitted:

L. Scott Paynter Reg. No. 39,797 Krieg DeVault LLP

One Indiana Square, Suite 2800 Indianapolis, Indiana 46204-2079

Telephone: (317) 238-6321 Facsimile: (317) 636-1507